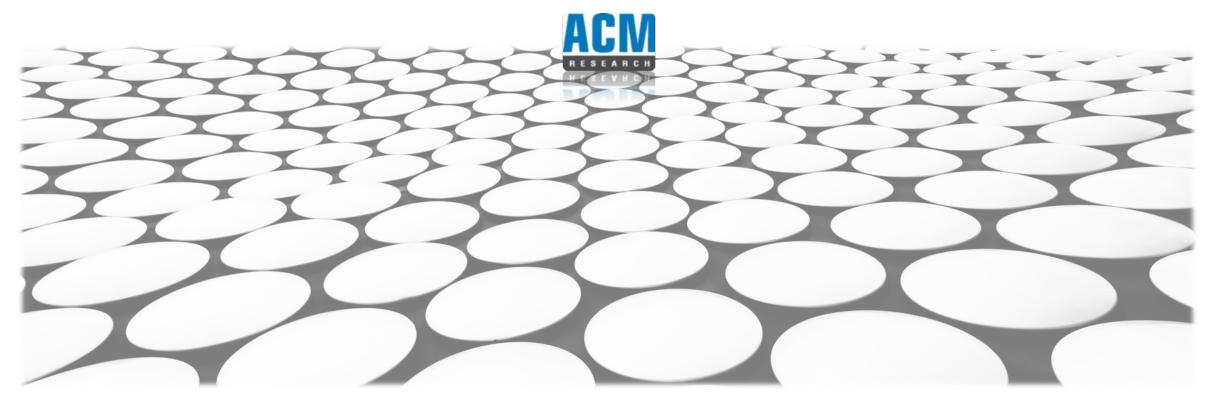


ADVANCED PRODUCTION TOOLS FOR LEADING EDGE IC FABS

Advanced wafer cleaning technologies



March 2024

DISCLOSURES

Forward-Looking Statements. Certain statements contained in this presentation are not historical facts and may be forward-looking statements within the meaning of the Private Securities Litigation Reform Act of 1995. Words such as "plans," "expects," "believes," "anticipates," "designed," and similar words are intended to identify forward-looking statements. Forward-looking statements are based on ACM Research management's current expectations and beliefs and involve a number of risks and uncertainties that are difficult to predict and that could cause actual results to differ materially from those stated or implied by the forward-looking statements. A description of certain of these risks, uncertainties and other matters can be found in filings ACM Research makes with the U.S. Securities and Exchange Commission (the "SEC"), all of which are available at www.sec.gov. Because forward-looking statements involve risks and uncertainties, actual results and events may differ materially from results and events currently expected by ACM Research. Readers are cautioned not to place undue reliance on these forward-looking statements, which speak only as of the date hereof. ACM Research undertakes no obligation to publicly update these forward-looking statements to reflect events or circumstances that occur after the date hereof or to reflect any change in its expectations with regard to these forward-looking statements or the occurrence of unanticipated events.

Market Data. Information presented below concerning ACM Research's total addressable market presents a forecast based on information provided by Gartner, Inc. in its report "Forecast: Semiconductor Wafer Fab Equipment, Worldwide, 4Q23 Update" (December 2023). You are cautioned not to rely on or give undue weight to this information. The Gartner report represents research opinions or viewpoints that are published, as part of a syndicated subscription service, by Gartner and are not representations of fact. The Gartner report speaks as of its original publication date (and not as of the date of this presentation), and the opinions expressed in the Gartner report are subject to change without notice. While ACM Research is not aware of any misstatements regarding the information provided in the Gartner report, it has not independently verified the accuracy or completeness of that information, which involves numerous assumptions and is subject to risks and uncertainties, as well as change based on various factors, that could cause results to differ materially from the forecast presented. The industry in which ACM Research operates is subject to a high degree of uncertainty and risk due to variety of factors, including those described in ACM Research public filings with the SEC, as described above.

Note Regarding Presentation of Non-GAAP Financial Measures. Information presented below under "Q4 and 2023 Summary" includes certain "non-GAAP financial measures" as defined in Regulation G under the Securities Exchange Act of 1934, including non-GAAP gross margin, non-GAAP operating income, non-GAAP basic and diluted EPS, and non-GAAP gross profit. These supplemental measures exclude the impact of stock-based compensation and unrealized gain or loss on short term investments, which ACM Research does not believe are indicative of its core operating results. A reconciliation of each non-GAAP financial measure to the most directly comparable GAAP financial measure is included below under "2023 GAAP to Non-GAAP Reconciliation." ACM Research believes these non-GAAP financial measures are useful to investors in assessing its operating performance. ACM Research uses these financial measures internally to evaluate its operating performance and for planning and forecasting of future periods. Financial analysts may focus on and publish both historical results and future projections based on the non-GAAP financial measures. ACM Research also believes it is in the best interests of investors for ACM Research to provide this non-GAAP information.

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Company References. As used in this presentation, "ACM Shanghai" refers to ACM Research (Shanghai), Inc., "ACM South Korea" refers to Hanguk ACM CO., LTD, and "ACM Research" refers to ACM Research, Inc. and its subsidiaries, including ACM Shanghai and ACM South Korea.

ACM Research at a Glance



- Multi-product supplier of semiconductor capital equipment to leading global semiconductor manufacturers
- **Differentiated technology** improves customer production processes with better yields and reduced chemical consumption
- More than 498 patents issued in the U.S., China, Japan, Singapore, South Korea and Taiwan as of 12/31/23
- **State-of-the-art production facilities** in Chuansha & ZhangJiang, Shanghai; construction in process for new R&D and production center in Lingang, Shanghai
- **Headquartered in Fremont, CA** with more than 1,590 employees globally as of 12/31/23

Cleaning

Flagship (SAPS, TEBO, Tahoe)







Semi-Critical

ECP, Furnace & Other

Ultra ECP ap

Ultra ECP map

Ultra Fn Furnace







NEW Products: Track and PECVD

Track

PECVD





Advanced Packaging & Other

Scrubbers, coaters, developer tools, plating tools, wet stripping, wet etching and stress-free polishing systems, and other parts and services

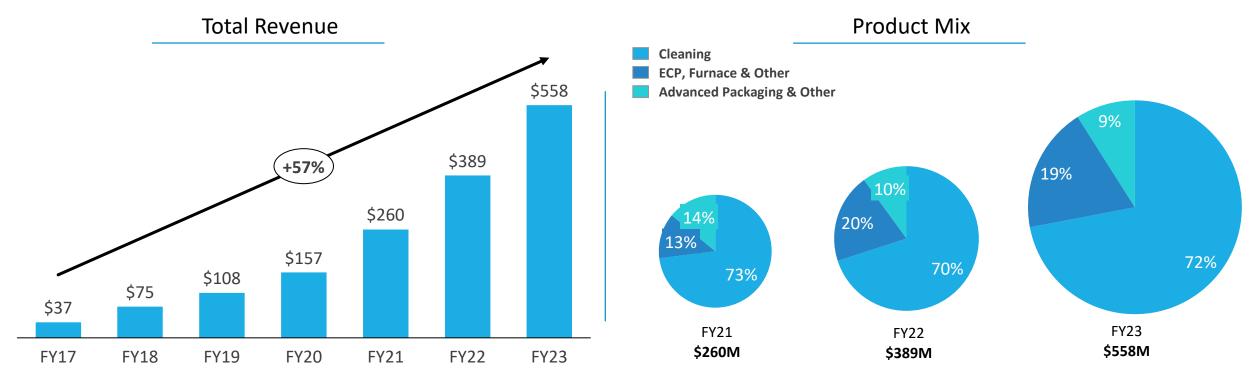






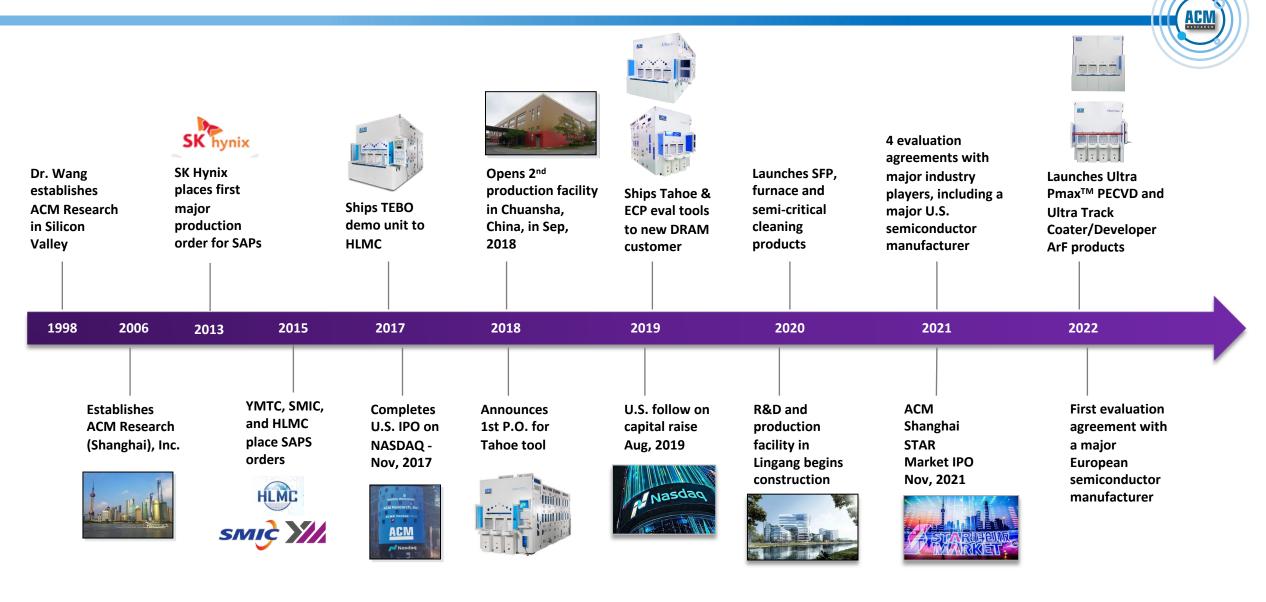
Financial Highlights





- 1. Cleaning: Single wafer cleaning, Tahoe and semi-critical cleaning equipment
- 2. ECP, Furnace & Other: ECP (front-end and packaging), furnace and other technologies
- 3. Advanced Packaging & Other: Advanced Packaging (excluding ECP), services & spares

History of Innovation and Customer Design Wins



Global Semiconductor Capital Equipment Supplier







Shanghai R&D Center (Zhangjiang)



Shanghai Asia-Pacific Manufacturing Center >200,000 ft² (Chuansha)



Planned >1.4 million ft² (Lingang)

Tier 1 Customer Base



Front-End Customers



- ACM 2023 Revenue %: 18%
- Mainland China's largest foundry
- Tier-one customers include Qualcomm, Broadcom and Texas Instruments
- 7 strategically located fabs in China
- Building 3 12-inch fabs in China (1)
- SMIC Shenzhen entered into production by the end of 2022 ⁽¹⁾



- ACM 2023 Revenue %: 15%
- A semiconductor integrated circuit developer in China



- ACM 2023 Revenue %: 13%
- New China-based entrant to DRAM industry

Back-End Customers



- Largest bumping house in China and leading WLCSP production base
- Subsidiary of OSAT company JCET
- Owns one of the most advanced packaging technology R&D service platforms⁽³⁾
- Global customer base with exposure to the U.S., Western Europe and Asia



- Major new entrant into NAND flash and DRAM industry
- Innovative Xtacking 2.0 unleashes potential of 3D NAND (2)



Leading advanced foundry in China

Tier 2 and 3 China-based IC Manufacturers

- Tier 2 includes Hangzhou Silan and 4 China-based customers
- Ordered a range of semi-critical tools including the scrubber, wet etch, and backside wafer etching tool, auto wet bench, SAPS-II cleaning tool and Cu interconnect ECP map tool.
- Tier 3 includes a handful of companies investing in new capacity in IoT, EV, AI

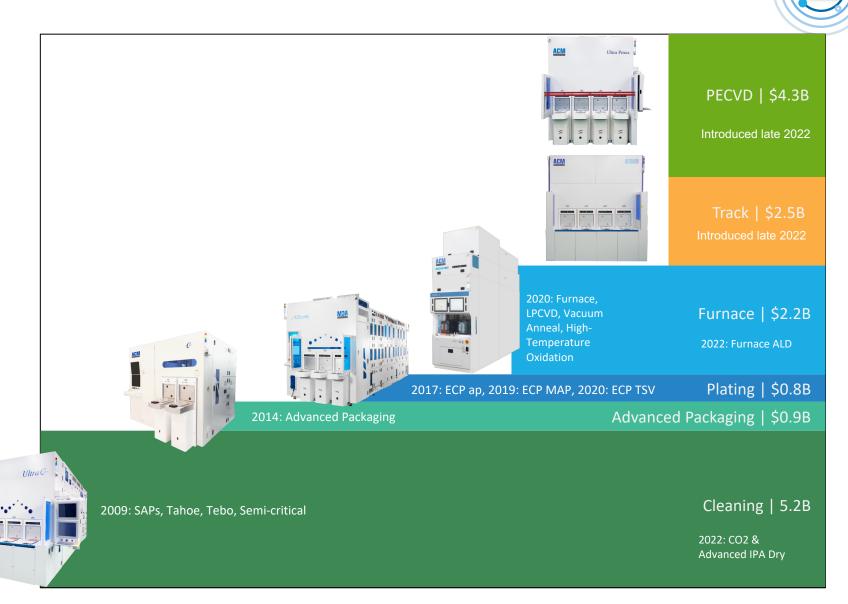


- Leading OSAT provider #4 globally⁽⁴⁾ and top 3 in China⁽⁴⁾
- Fastest growing OSAT provider globally with ~30% year-over-year revenue growth in 2022⁽⁴⁾
- Six production facilities serving more than half of the top ten global semiconductor manufacturers⁽⁴⁾

(1) Source: SMIC website. (2) Source: YMTC Press Release. (3) Source: JCAP Company Profile. (4) Source: TFME website.

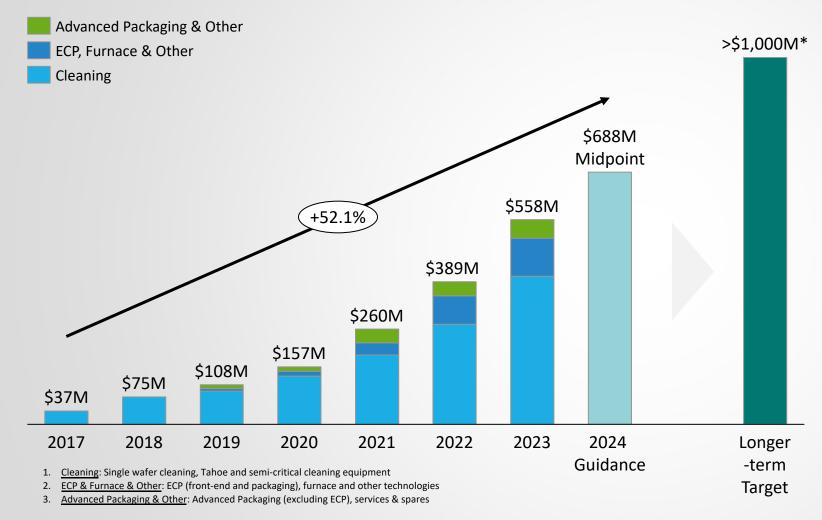
Innovative Product Introductions Expanding Serviceable Available Market ("SAM")

Estimated 2023 SAM of \$16 billion addressed by ACM's current product portfolio



Longer-Term Target for \$1B+ in Revenue





		ACM Research							
Mainland China	SAM ¹	Share	Revenue						
Cleaning	\$0.8B	55%	\$0.4B						
ECP	\$0.2B	50%	\$0.1B						
Furnace	\$0.3B	35%	\$0.1B						
PECVD	\$0.7B	15%	\$0.1B						
Track	\$0.4B	15%	\$0.1B						
Ad. Packaging	n/a	n/m	\$0.2B						
	\$2.4B	40%	\$1.0B						
RoW									
Cleaning	\$4.4B	-							
ECP	\$0.6B	-	Upside						
Furnace	\$1.9B	-							
PECVD	\$3.7B	-	_						
Track	\$2.1B	_	-						
Ad. Packaging	n/a	-	-						
	\$12.6B	_	Upside						

¹Source: Gartner - "Forecast: Semiconductor Wafer Fab Equipment, Worldwide, 4Q23 Update" (December 2023) and Company Estimates:

- 2023 Gartner WFE market of \$93B
- ACM Global SAM is ~17% of Global WFE and China is 28% of ACM Global SAM

^{*} ACM longer-term internal target, for internal planning purposes only, not a projection or estimate of actual or future revenue

Growth Strategy



Growth at Existing Customers

- Continue winning share at existing customers
- Continued China fab expansion, particularly in mature nodes
- Accelerating ECP and furnace product cycles

International Expansion

- Expanding dedicated sales team in U.S. and Europe
- SAPS cleaning tool qualified for revenue by a large US manufacturer
- Installed SAPS evaluation tool at major Europe-based global semiconductor manufacturer
- Good progress with Track tool evaluation at customer site
- Expect significant progress for PECVD product development and evaluations in 2024.

New Capacity

- Lingang facility on track for initial production for mid-2024 with target for annual revenue production capacity over \$1.5 billion
- Purchased new headquarters in Zhangjiang Shanghai, Silicon Valley of China
- Korea R&D and production facility to support international expansion
- 2023 ~\$100 million capex



New Products

- Broad cleaning portfolio covers 90%+ with addition of semi-critical, bevel etch, high-temp SPM, and super-critical dry CO2.
- Plating for front and back end, furnace and semi-critical tools
- Added Track & PECVD product categories at end of 2022 that doubled our SAM to \$16 billion



Q4 and 2023 Summary



Key Operational Updates

- Solid growth amid declining global WFE.
- SAPS cleaning tool qualified for revenue by a large US manufacturer.
- Installed SAPS evaluation tool at major Europe-based global semiconductor manufacturer.
- Good progress with Track tool evaluation at customer site.
- Expect significant progress for PECVD product development and evaluations in 2024.
- Construction of Lingang production and R&D center nearly complete; initial production in mid-2024.

Q4 2023 Financial Results

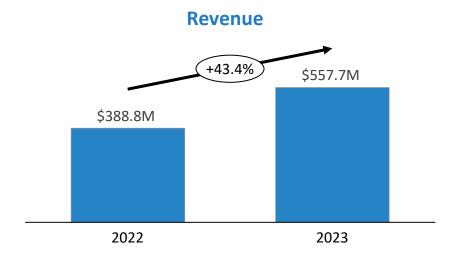
- \$170.3 million revenue (up 56.9% y/y); total shipments of \$140 million (down 29% y/y)
- 46.8% non-GAAP gross margin (versus 49.7% in Q4 2022)
- \$36.0 million non-GAAP operating income (21.2% of revenue)

2023 Financial Results

- \$557.7 million revenue (up 43.4% y/y); total shipments of \$597 million (up 11% y/y)
- 49.5% GAAP gross margin (versus 47.2% in Q4 2022)
- 49.8% non-GAAP gross margin (versus 47.4% in Q4 2022)
- \$95.8 million GAAP operating income (17.2% of revenue)
- \$123.2 million non-GAAP operating income (22.1% of revenue)
- \$1.16 diluted GAAP earnings per share (versus \$0.59 in Q4 2022)
- \$1.63 diluted non-GAAP earnings per share (versus \$0.83 in Q4 2022)

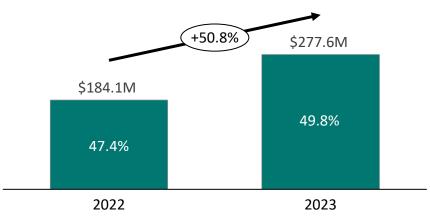
2023 Financial Results







Non-GAAP Gross Profit



Balance Sheet

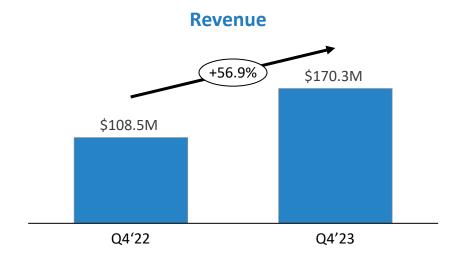


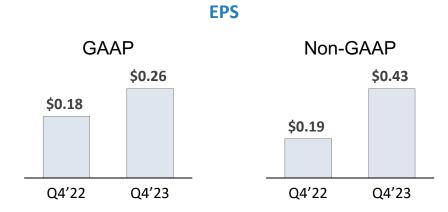
¹ Including interest bearing time deposits.

See slide 21 for reconciliation between GAAP and Non-GAAP Gross Profit and EPS.

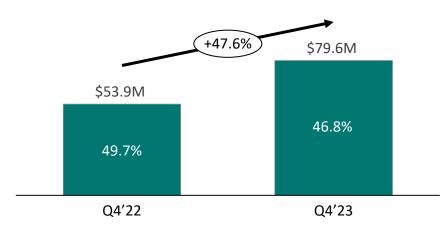
Q3 2023 Financial Results











Balance Sheet



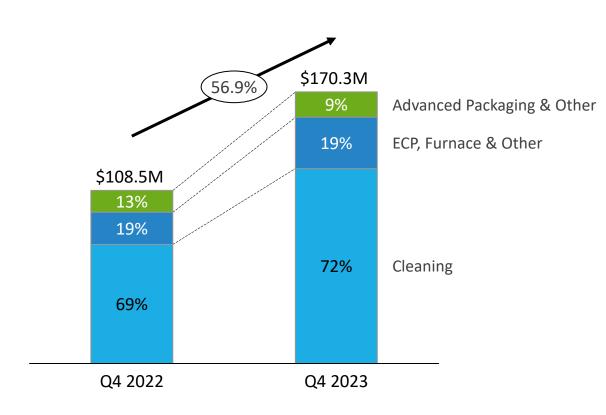
¹ Including interest bearing time deposits.

See slide 22 for reconciliation between GAAP and Non-GAAP Gross Profit and EPS.

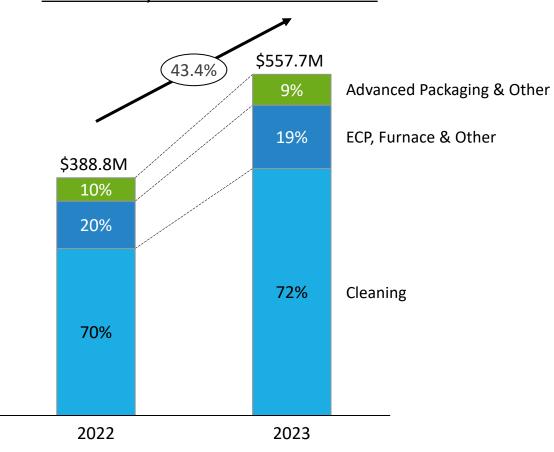
Q4 and 2023 Revenue Detail



Revenue by Product: Q4'23 vs Q4'22



Revenue by Product: 2023 vs 2022



^{1. &}lt;u>Cleaning</u>: Single wafer cleaning, Tahoe and semi-critical cleaning equipment

^{2. &}lt;u>ECP, Furnace & Other</u>: ECP (front-end and packaging), furnace and other technologies

^{3.} Advanced Packaging & Other: Advanced Packaging (excluding ECP), services & spares

Wafer Cleaning

Flagship Cleaning Tools

SAPS

Megasonic Cleaning for Flat and Patterned Wafer Surfaces

- High efficiency with enhanced process flexibility
- Uniform and consistent results
- Customizable specifications

TEBO



Bubble Oscillation Cleaning for Patterned Wafers at Advanced Process Nodes

- Highly effective, damage-free solution for small and fragile features
- Multi-parameter bubble cavitation control

Ultra - C Tahoe



Hybrid Wafer Cleaning With Significant Cost & Environmental Benefits

- Environmentally friendly uses 10% of the sulfuric acid used than conventional tools
- O High cleaning performance at low cost

Bevel Etch



Bevel Etching process for 3D NAND, DRAM and advanced logic processes

- Accurate and efficient wafer center alignment for precise bevel etch
- Variable wafer bevel etch/cut accuracy of 1-7mm and good uniformity

Single high tem SPM



Single High Temp SPM Cleaning for metal removal and PR Strip at advance node

Photoresist stripping after high-dose energy implant, wet stripping without using a dry ash process, and special metal film removal processes at advance node

Semi Critical Cleaning Tools

Auto Bench



Batch Wafer Cleaning for a full range of wet technologies across multiple nodes

- ULD advance drying technology addresses challenges in high-aspect-ratio structures
- MCR module delivers high cleaning performance

Backside



Backside Clean Tool for wafer device side none contact process

- Good particle performance and etch uniformity

Scrubber



Scrubber Cleaning for efficient frontand backside wet-cleaning applications

 High throughput, small footprint and low cost Small particle removal

Advance Processes

Supercritical CO2 Dry



Supercritical CO2 Dry for advance DRAM processes

Damage free drying process for high aspect-ratio structures including Isolation

High Temp IPA Dry (UTD)



High Temp IPA Drying for advance Logic processes

- Damage free drying process for small structures and high-aspect-ratio structures Associate with customizable Cleaning
- method for good cleaning performance

Electroplating













	Model	Ultra ECP map	Ultra ECP 3D	Ultra ECP ap	Ultra ECP ap (Cu-Ni-SnAg-Au)	Ultra ECP GIII
A	Application	Dual-damascene plating (90nm-28nm)	3D/2.5D high aspect ratio TSV	Pillar bump, Solder bump, RDL, Conformal TSV	High-density Fan Out Fine Pitch RDL	RF product 150mm wafer-level packaging
		16 chambers	10/12 chambers	24/28 chambers	28 chambers	8/9 chambers
	Module	Cu Post-cleaning Annealing	Cu Post-cleaning Pre-wetting	Cu+Ni+SnAg Pre-wetting Post-cleaning	Cu/Ni/SnAg/Au Pre-wetting Post-cleaning Cleaning after Au plating	Cu+Sn/Ag+Ni Au Pre-wetting Post-cleaning
	Special Features	Impulse local plating	Impulse local plating	Second anode technology	Second anode technology Impulse Au plating	Second anode technology

Vertical Furnace



Mask

Ox | Photo | Exposure | Develop | Etch | Ion | CVD | ALD | Metal | Wire |

Furnace Tube Classification	Film Type	Process	Temperature Range	Existing ACM Product	In Development
	Oxidation	Wet oxygen/dry	700~1200°C	*	
Normal Pressure	Annealing	oxygen/nitrogen annealing	700 1200 C	*	
Chemical Vapor Deposition Furnace	Back-end thermal	Copper process thermal treatment	100~450°C		
	treatment	Coating and curing	100 430 9		
	Alloy	Hydrogen/nitrogen thermal treatment	100~450°C	*	
		Poly-crystal silicon doping		*	
Low Pressure Chemical Vapor	Silicon deposition	Advanced poly-crystal deposition	500~620°C		☆
Deposition Furnace		No poly-crystal silicon doping		*	
	Silicon oxide	High-temperature silicon oxide	C50~200°C	*	
	Silicon nitride	Silicon nitride deposition	650~800°C	*	
Atomic Layer	Silicon oxide	Silicon oxide deposition	500~650°C	.	
Deposition Furnace	Silicon nitride	Silicon nitride deposition	500°650 G	*	



W*L*H= 1.10m*3.70m*4.05m

Advanced Packaging



Comprehensive solution for wafer-level advanced packaging wet process

Cleaning

Scrubber

- Make use of ACM Research's technology advantages to expand application in Asia, especially advanced packaging manufacturers in China
- Dedicated to providing diversified and customer equipment meeting customer's designing requirements
- The products include scrubbers, coaters, developers, photoresist strippers, wet etchers, ECPs, and stress-free polishers

Coating



Coater

Wet Etching



Wet Etcher

Developing



Developer





PR stripper

Plating



ECP

Planarization



SFP

Track and PECVD



Model	Model	Technical Features	Offline/Inline	Chamber Temperature	Bake Range	Development Phase
Ultra Lith™ Track	ArF Model	 ✓ Support 300mm wafers ✓ Four 12-inch load ports ✓ 8 coating chambers ✓ 8 developing chambers 	Inline	23°C ±0.1°C	50~250°C	Industry Evaluation
Coater/Developer — —	KrF Model					In Development
	I-line Model					In Development

Model	Film Category	Film Type	RF Frequency	RF Control	Heater/CH	Development Phase
ACM Ultra Pmax	SiH4 Base	SiO2; Si3N4; SiON	HF: 13.56MHz HF: 27.12MHz LF: 400KHz	Separate control	3	
	TEOS Base TEOS Layer	TEOS Layer	HF: 13.56MHz HF: 27.12MHz LF: 400KHz	Separate control	3	Industry Evaluation
Ultra Pmax [™] PECVD	Chemical Base	SiCN/APF Layer	HF: 13.56MHz HF: 27.12MHz LF: 400KHz	Separate control	3	

2023 GAAP to Non-GAAP Reconciliation



							Year	Ended De	cem	ber 31,								
				2	2023						2022							
		Actual (GAAP)				SBC	Other non- operating adjustments		Adjusted (Non-GAAP)		Actual (GAAP)			SBC	Other non- operating adjustments			Adjusted on-GAAP)
					aujustii	ients		(In thous	an de	,)			auj	ustilients	Ì			
								(In thouse	ınus	,								
Revenue	\$	557,723	\$	-	\$	- 9	\$	557,723	\$	388,832	\$	-	\$	-	\$	388,832		
Cost of revenue		(281,508)		(1,406)		-		(280,102)		(205,217)		(520)		-		(204,697)		
Gross profit		276,215		(1,406)		-		277,621		183,615		(520)		-		184,135		
Gross margin		49.5%		0.3%		-		49.8%		47.2%		0.1%		-		47.4%		
Operating expenses:																		
Sales and marketing		(47,019)		(5,684)		-		(41,335)		(39,889)		(1,877)		-		(38,012)		
Research and development		(92,709)		(8,459)		-		(84,250)		(62,226)		(2,565)		-		(59,661)		
General and administrative		(40,648)		(11,789)		-		(28,859)		(22,465)		(2,768)		-		(19,697)		
Total operating expenses		(180,376)		(25,932)		-		(154,444)		(124,580)		(7,210)		-		(117,370)		
Income (loss) from operations	\$	95,839	\$	(27,338)	\$	- 5	\$	123,177	\$	59,035	\$	(7,730)	\$	-	\$	66,765		
Unrealized loss on short-term investments		(2,737)		-	(2	2,737)		-		(7,855)		-		(7,855)		-		
Net income (loss) attributable to ACM Research, Inc.	\$	77,349	\$	(27,338)	\$ (2	2,737) 5	\$	107,424	\$	39,263	\$	(7,730)	\$	(7,855)	\$	54,848		
Basic EPS	\$	1.29				9	\$	1.79	\$	0.66					\$	0.93		
Diluted EPS	\$	1.16				9	\$	1.63	\$	0.59					\$	0.83		

Q4 2023 GAAP to Non-GAAP Reconciliation



Three	Mont	hs F	Inded	Decen	nber í	31.

				2023											
		Actual			Other non- BBC operating adjustments		Adjusted		Actual				Other non-	A	Adjusted
	((GAAP)		SBC				(Non-GAAP)		(GAAP)		SBC	operating adjustments	(Non-GAAP)	
								(In thousa	ınds)					
Revenue	\$	170,321	\$	-	\$	-	\$	170,321	\$	108,542	\$	-	\$ -	\$	108,542
Cost of revenue		(91,245)		(568)		-		(90,677)		(54,737)		(137)	-		(54,600)
Gross profit		79,076		(568)		-		79,644		53,805		(137)	-		53,942
Gross margin		46.4%		0.3%		-		46.8%		49.6%		0.1%	-		49.7%
Operating expenses:															
Sales and marketing		(9,440)		(2,279)		-		(7,161)		(12,395)		(600)	-		(11,795)
Research and development		(32,465)		(3,628)		-		(28,837)		(17,835)		(832)	-		(17,003)
General and administrative		(13,797)		(6,197)		-		(7,600)		(6,905)		(925)	-		(5,980)
Total operating expenses		(55,702)		(12,104)		-		(43,598)		(37,135)		(2,357)	-		(34,778)
Income (loss) from operations	\$	23,374	\$	(12,672)	\$	-	\$	36,046	\$	16,670	\$	(2,494)	\$ -	\$	19,164
Unrealized gain on short-term in vestments		1,691		-	1,	691		-		1,707		-	1,707		-
Net income (loss)	\$	17,700	\$	(12,672)	\$ 1,	691	\$	28,681	\$	11,809	\$	(2,494)	\$ 1,707	\$	12,596
attributable to ACM Research, Inc.															
Basic EPS	\$	0.29					\$	0.47	\$	0.20				\$	0.21
Diluted EPS	\$	0.26					\$	0.43	\$	0.18				\$	0.19